

ATTORNEY DOCKET NO. 07977/052001/US3053

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Hisashi Ohtani et al.

Art Unit: 1765

Serial No.: 08/690,747

Examiner: R. Kunemund

Filed

: August 1, 1996

Title : METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE

Box AF

Assistant Commissioner for Patents

Washington, DC 20231

## **AMENDMENT**

Sir:

In response to the Official Action dated April 7, 1999, paper no. 9 in the above-referenced case, kindly amend the abovereferenced application as follows:

## In the Claims

Please amend the claims as follows.

(Amended) A method for manufacturing a semiconductor device comprising the steps of:

forming a non-single crystalline semiconductor film to become at least a channel forming region on an insulating surface;

patterning said semiconductor film into a patterned semiconductor film having peripheral portions;

Date of Deposit

Deborah Dean

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated above and is addressed to the Assistant Commissioner for Parent **2023**1.